



Child Victims Act: Litigation and Coverage Concerns

October 30, 2019

1:00 p.m. – 2:15 p.m.

BAEC, 438 Main St., Sun Room Auditorium, Buffalo

1.5 CLE credits: 0.5 Areas of Professional Practice, 1.0 Skills (approved for all attorneys)

Speakers:

Anastasia M. McCarthy, Esq., *Hurwitz & Fine, PC*

Brian D. Barnas, Esq., *Hurwitz & Fine, PC*

This 75-minute seminar will include an overview of the Child Victims Act, the various legal and practical issues arising from recent litigation, and the insurance coverage implications of Child Victims Act claims and lawsuits.

Erie Institute of Law Registration Form – Child Victims Act: Litigation and Coverage Concerns

\$35 BAEC Member

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Mail or scan to: Erie Institute of Law, 438 Main Street, Sixth Floor, Buffalo, New York 14202, (716) 852-8687, or scan to cwalsh@eriebar.org. Register online at www.eriebar.org. Walk-in registrants add \$5 to registration fee. Tuition assistance available. Please call to request an application.